

Supporting Information

A general strategy for enhancing photoluminescence of TMD quantum sheets

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Experimental Section

Material: All chemicals and analytical reagents were utilized in their original form without additional purification. Tungsten disulfide (powder, 99.99%), molybdenum diselenide (powder, 99.99%), tungsten diselenide (powder, 99.99%), and bismuth selenide (powder, 99.99%) were purchased from Aladdin Bio-Chem Technology Co., Ltd. Potassium bromide (SP, 99.5%) was purchased from Tianjin Tianguang Optics Instrument Co., Ltd. Tetrahydrofuran (THF) (SP, 99.5%), N-methyl-2-pyrrolidone (NMP) (AR), aqueous ammonia (25%-28%), dichloroethane (AR), tetraethyl orthosilicate (AR), and poly(methyl methacrylate) (PMMA) (Transmittance > 92%) were purchased from Shanghai Macklin Biochemical Co., Ltd. Isopropanol (AR) and n-hexane (AR) were purchased from Tianjin Damao Chemical Reagent Factory. Porous anodic alumina (PAA) (0.02 μm pore size) was purchased from Whatman. The commercial InGaN chips and thermal-curable silicone resin were purchased from Sanan Optoelectronics Co., Ltd.

Synthesis of intrinsic quantum sheets (I-QSs): The I-QSs were prepared by a combination of silica-assisted ball-milling and sonication-assisted solvent exfoliation.¹ Initially, 200 mL of ethanol was heated to 70°C and stirred, then 40 mL of tetraethyl orthosilicate was added. The mixture was stirred and heated for 20 minutes. Next, 40 mL of ammonia and 40 mL of water were added, with heating and stirring for 2 hours. The mixture was centrifuged, washed with ethanol, and vacuum-dried to produce 450 nm silica microspheres. A mixture of TMD powders (0.7 g), silica microspheres (7 g), and agate balls (70 g) were ball-milled at 500 rpm for 12 hours. After ball-milling, the agate balls were removed. The mixture was dispersed in NMP with a concentration of approximately 55 mg/mL for sonication (Vibra-Cell Ultrasonic Liquid Processor, VCX800, SONICS) at 240 W for 5 hours. The TMD QSs filtrate were collected through centrifugation and PAA membrane with a 0.02 μm pore size. The TMD QSs powders were obtained by preparing a precipitation system with a volume ratio of 5/10/2 (QSs filtrate/n-hexane/IPA) and centrifuged at 8000 rpm for 30 minutes, followed by vacuum drying.

Synthesis of passivation quantum sheets (P-QSs): P-QSs were prepared by redispersing the I-QSs powder in THF (concentration of 0.04 mg/mL), and then heated in silicone oil at 100°C for 4 hours at a constant temperature. The TMD QSs

were washed with dichloroethane 2 times after heating, then vacuum drying (50°C, 2 hours). Subsequently, 1 mL of NMP dispersant was added to redisperse the Qs. Ultrasonic treatment at 100 W for 10 minutes (using a 200 W ultrasonic cleaning machine) was performed to obtain passivated Qs dispersion. All the Qs-PMMA thin films described in this study were fabricated in the following procedure: 400 mg PMMA were dissolved in 1 mL NMP and stirred at 50°C for 12 hours to prepare a 400 mg/mL polymer solution. Then, the passivated Qs dispersion and polymer solution were mixed by stirring at a loading amount of 0.1 wt% Qs (Qs/PMMA=1/1000). Finally, the solution was transferred to PTFE mold (0.4 ml in total capacity) and kept at 40°C for 24 hours.

Fabrication of Light Emitting Diodes (LEDs): The white LEDs were fabricated by coating P-WS₂ Qs on the commercial 382 nm InGaN chips. The passivated Qs (5 μL, 0.06 mg/mL in NMP) were coated on the InGaN LED chip and dried at 40°C for 12 hours. Subsequently, the thermal-curable silicone resin (15 μL) was coated on the surface of the Qs layer, followed by thermal curing at 40°C for 10 hours to obtain the solid-state white LEDs.

Characterization: The transmission electron microscopy (TEM) and high-resolution TEM (HRTEM) images were collected using the FEI Tecnai F20 U-TWIN microscope operating at an acceleration voltage of 200 kV. The atomic force microscope (AFM) images were performed utilizing the Bruker MultiMode 8 AFM. The X-ray diffraction (XRD) measurements were carried out on a D/Max-TTRIII (CBO) with Cu K α radiation ($\lambda = 1.54056 \text{ \AA}$). Fourier-transform infrared (FTIR) spectra were recorded on a PerkinElmer Spotlight 200i by potassium bromide tablet. X-ray photoelectron spectroscopy (XPS) analyses were performed utilizing an EscaLab 250Xi electron spectrometer from ThermoFisher Scientific, employing 300 W Al K α radiation. The ultraviolet-visible (UV-vis) absorption spectra were recorded using a Lambda 950 spectrophotometer from PerkinElmer. The photoluminescence (PL) and electroluminescence (EL) spectra were collected at room temperature on HORIBA FluoroMax Plus. A time-correlated single photon counting (TCSPC) method was employed to measure the PL lifetime using HORIBA FluoroMax Plus and TCSPC instrument. The instrument response function (IRF) was measured by

SiO₂. The photoluminescence quantum yield (PLQY) of TMD Qs were measured at room temperature by HORIBA FluoroMax Plus and integrating sphere attachment.

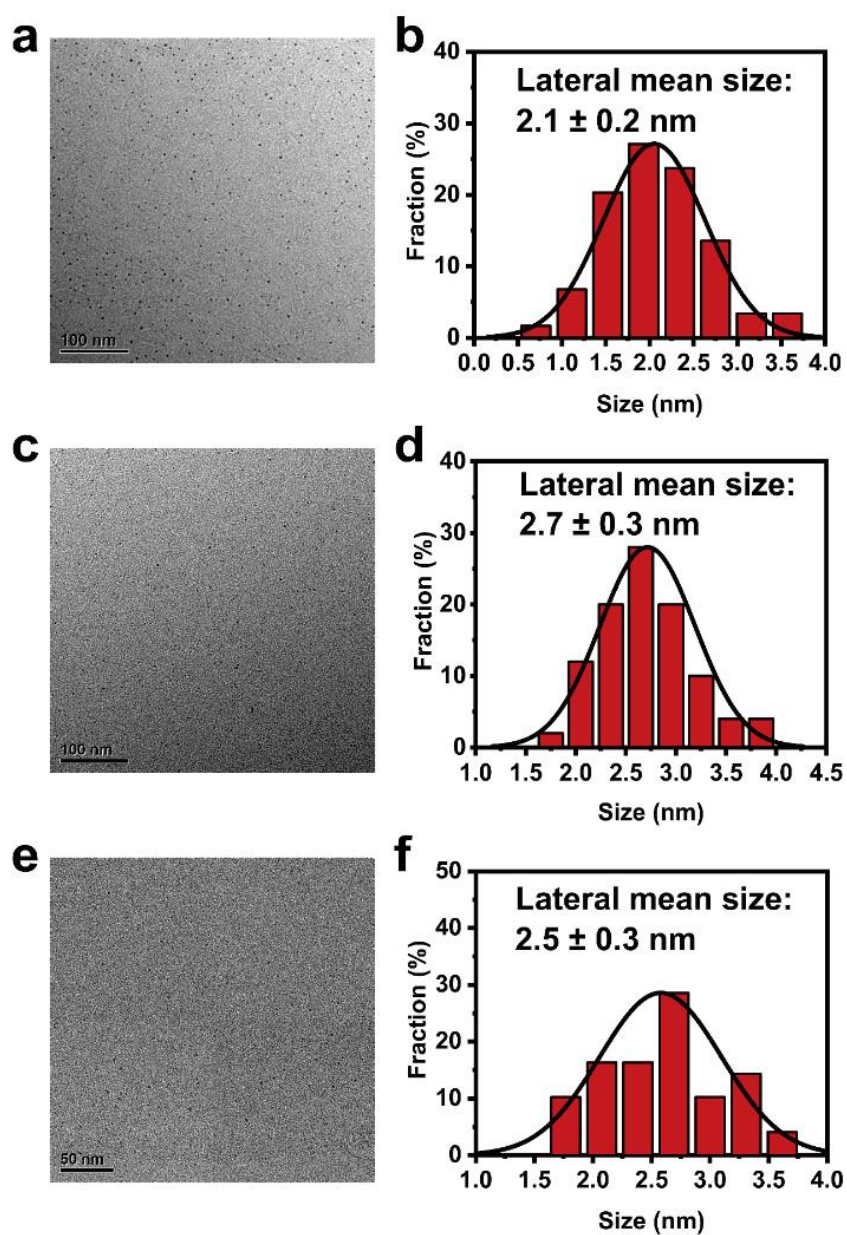


Figure S1. TEM-based measurement of the sizes of intrinsic QDs. (a) TEM image and (b) Size distribution of I-MoSe₂ QDs. (c) TEM image and (d) Size distribution of I-Bi₂Se₃ QDs. (e) TEM image and (f) Size distribution of I-WSe₂ QDs.

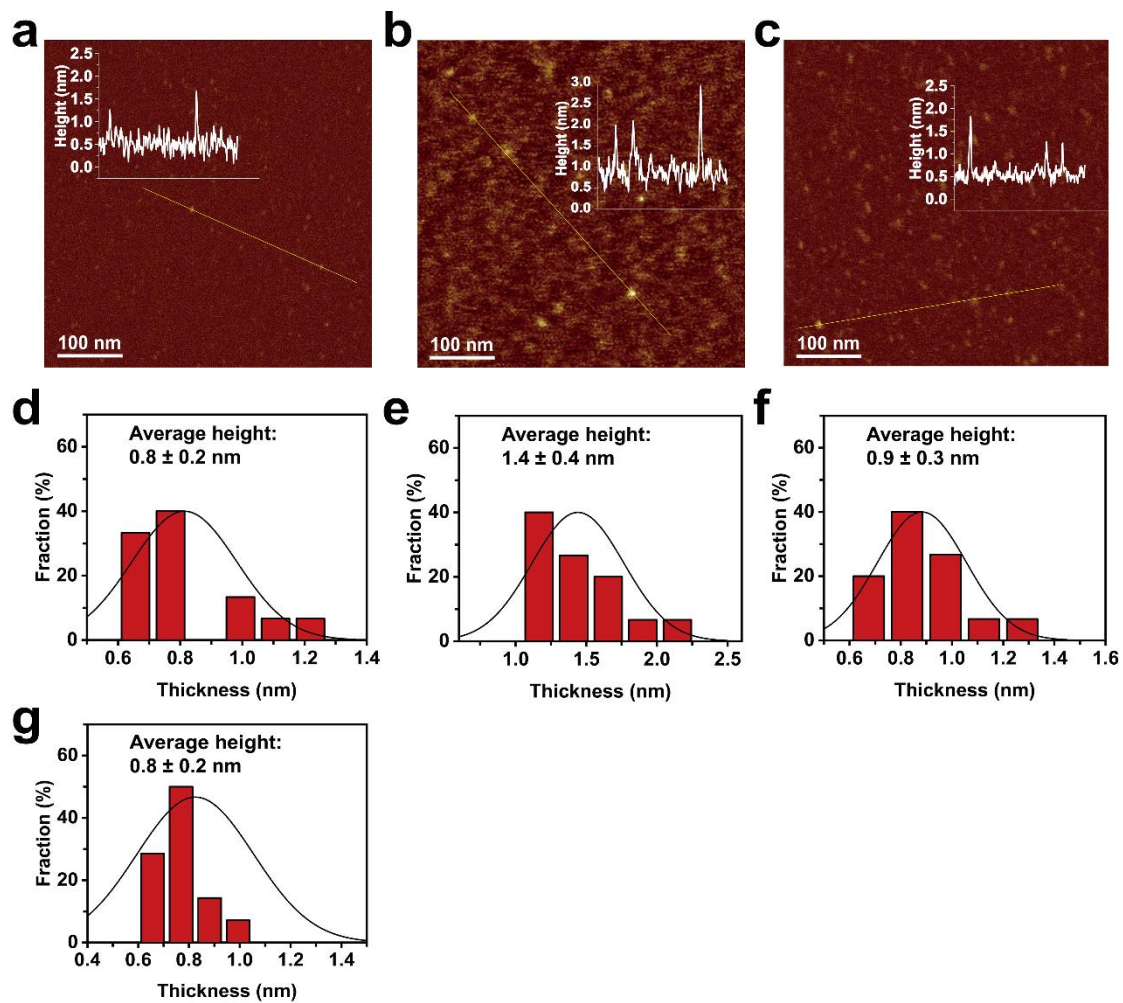


Figure S2. AFM images of (a) I-MoSe₂ QDs, (b) I-Bi₂Se₃ QDs, and (c) I-WSe₂ QDs. The average height of (d) I-MoSe₂ QDs, (e) I-Bi₂Se₃ QDs, (f) I-WSe₂, and (g) I-WS₂ QDs. The corresponding height profile along the line in the AFM images.

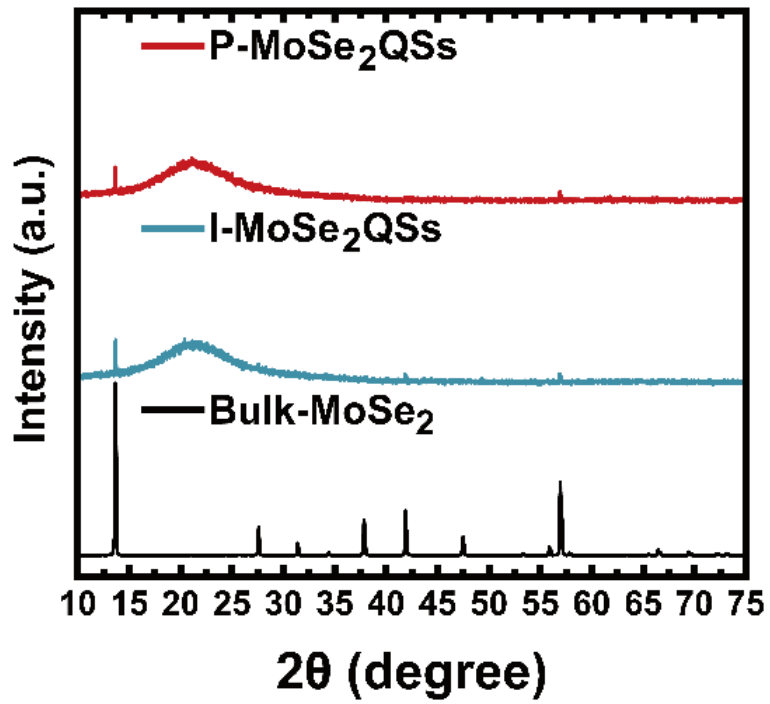


Figure S3. XRD patterns of MoSe₂.

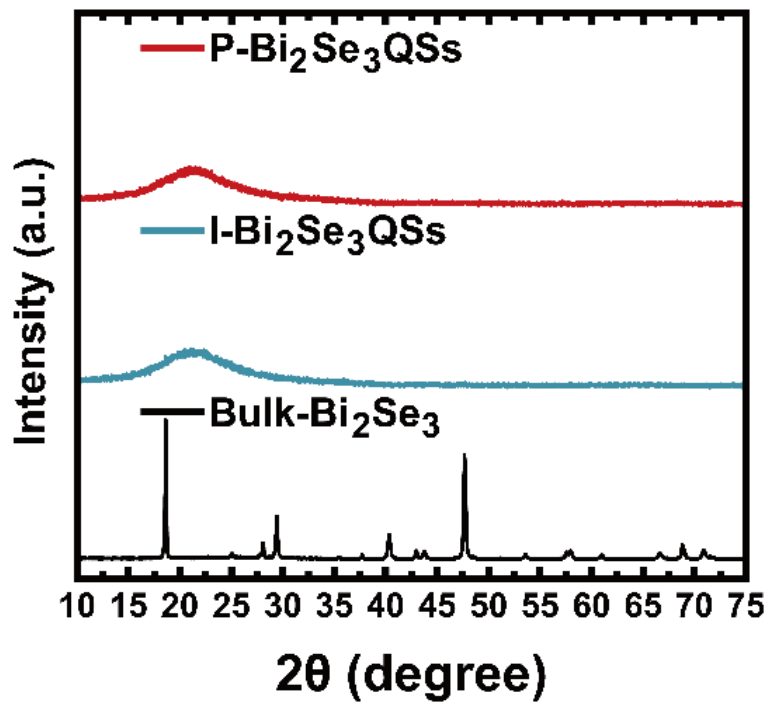


Figure S4. XRD patterns of Bi₂Se₃.

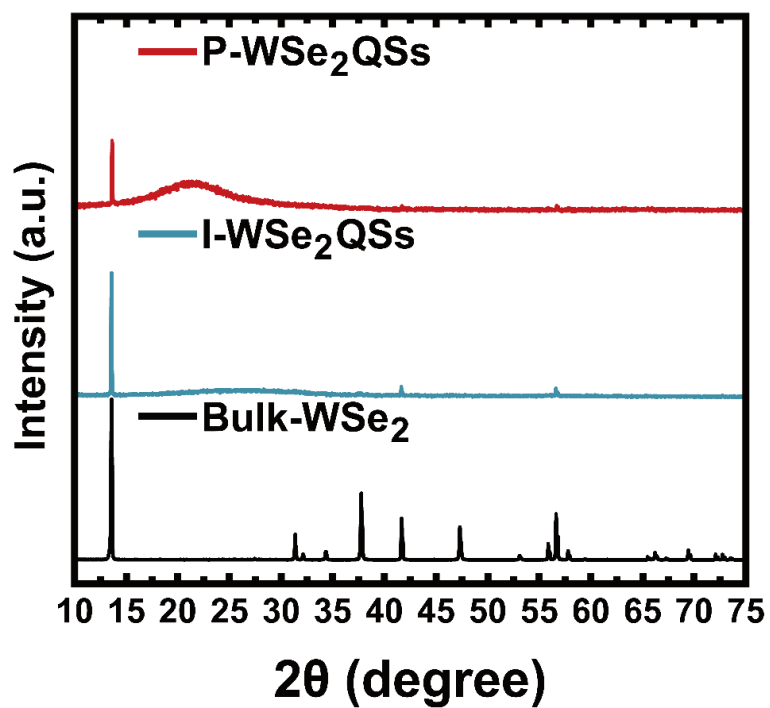


Figure S5. XRD patterns of WSe₂.

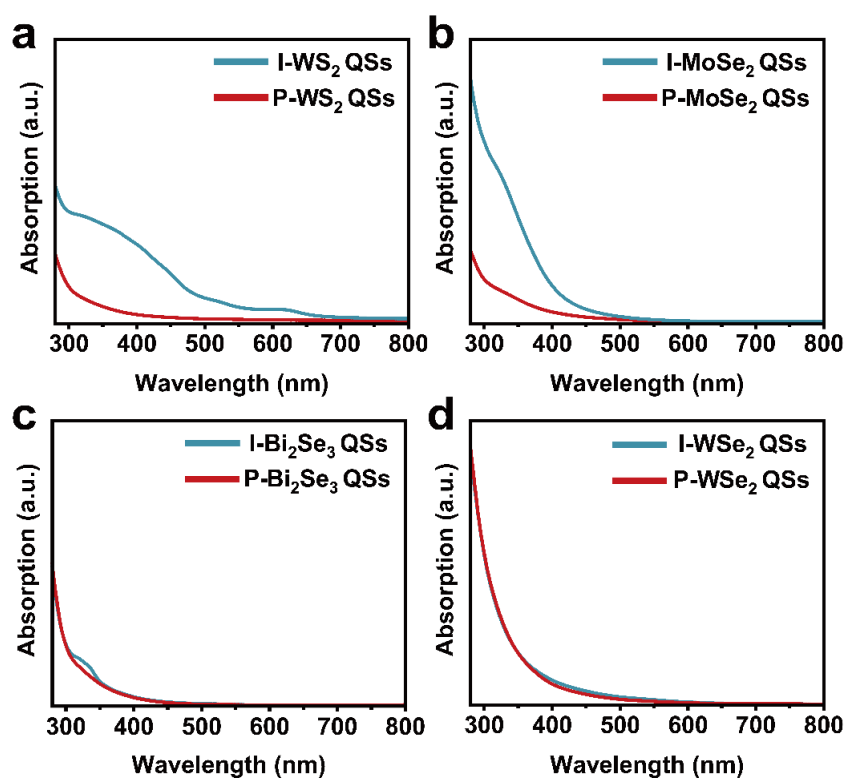


Figure S6. UV-vis absorption spectra of TMD QDs. (a) WS₂ QDs. (b) MoSe₂ QDs. (c) Bi₂Se₃ QDs. (d) WSe₂ QDs.

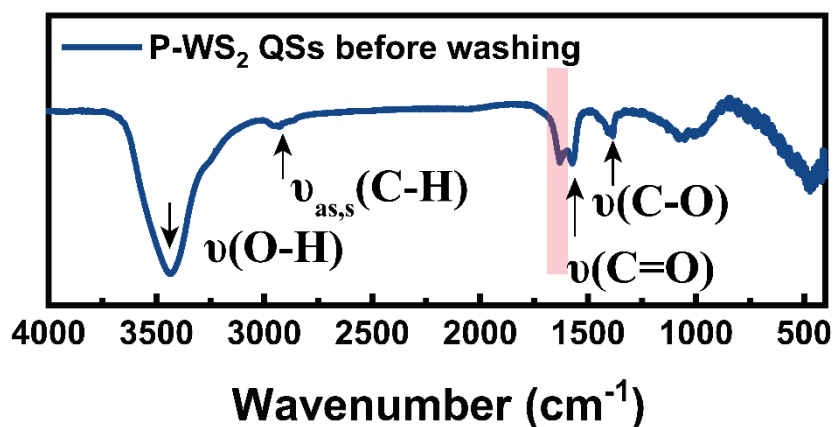


Figure S7. FTIR spectrum of WS₂ QDs before dichloroethane washing. ν_s: vibration modes for symmetric stretching. ν_{as}: vibration modes for asymmetric stretching. Red area: skeletal vibrations of aromatic ring.

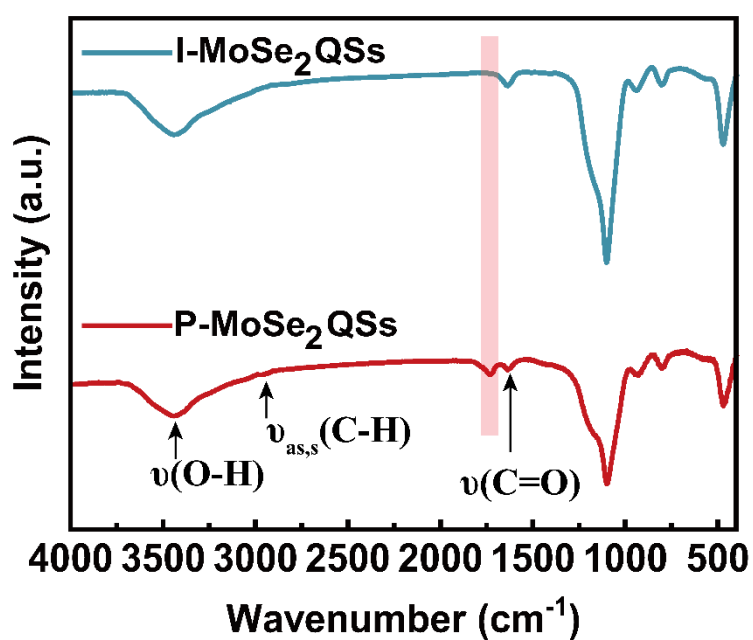


Figure S8. FTIR spectra of MoSe₂ QDs. ν_s: vibration modes for symmetric stretching. ν_{as}: vibration modes for asymmetric stretching. Red area: skeletal vibrations of aromatic ring.

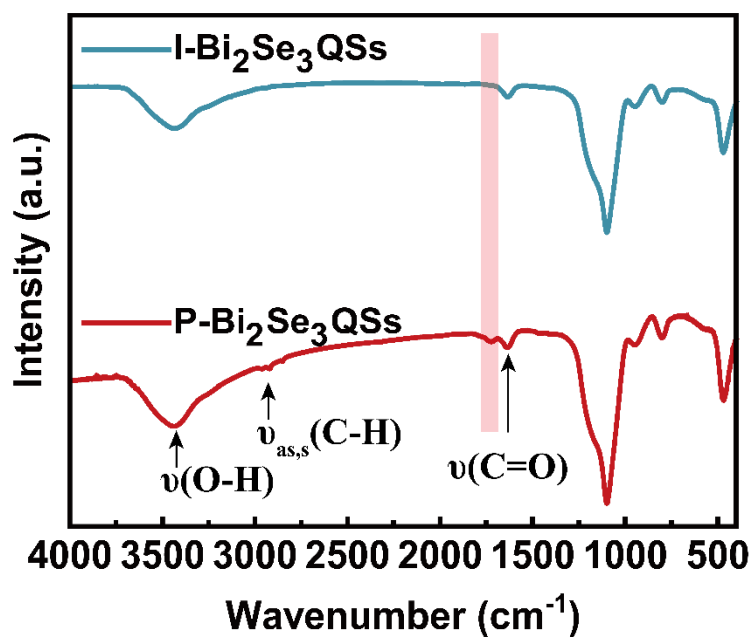


Figure S9. FTIR spectra of Bi_2Se_3 QDs. ν_s : vibration modes for symmetric stretching. ν_{as} : vibration modes for asymmetric stretching. Red area: skeletal vibrations of aromatic ring.

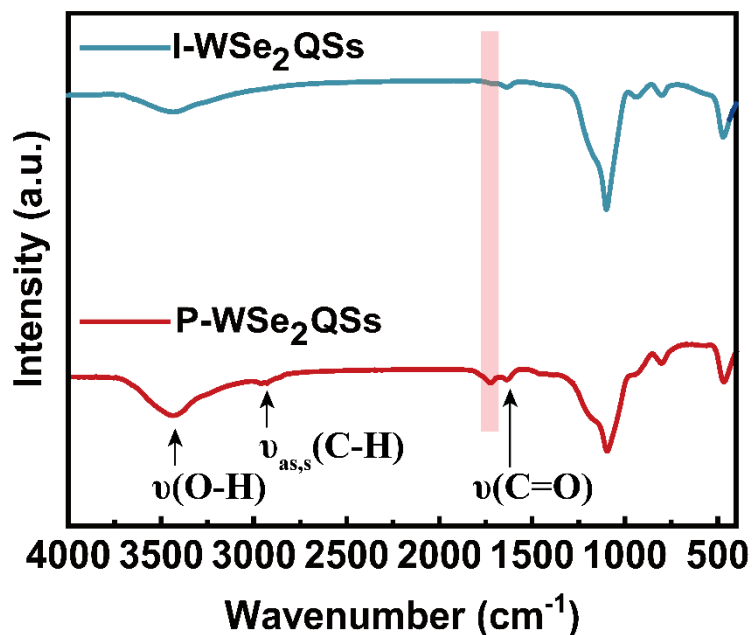


Figure S10. FTIR spectra of WSe_2 QDs. ν_s : vibration modes for symmetric stretching. ν_{as} : vibration modes for asymmetric stretching. Red area: skeletal vibrations of aromatic ring.

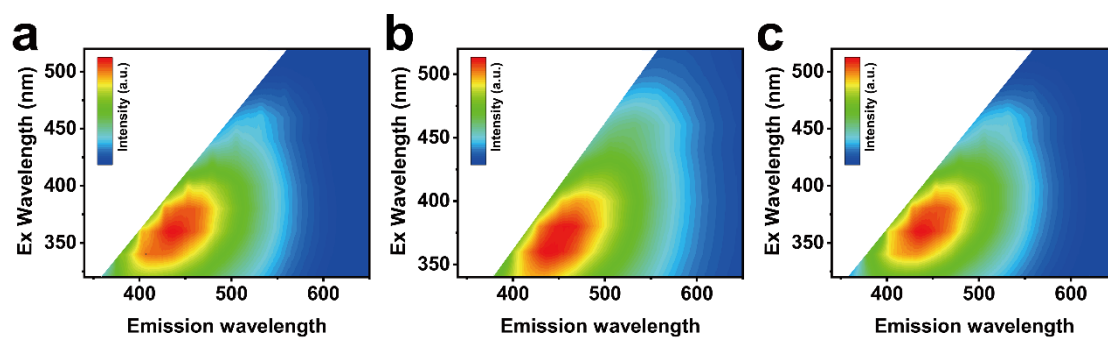


Figure S11. Excitation–emission matrices for P-QSs-PMMA. (a) P-MoSe₂ QSs-PMMA. (b) P-Bi₂Se₃ QSs-PMMA. (c) P-WSe₂ QSs-PMMA.

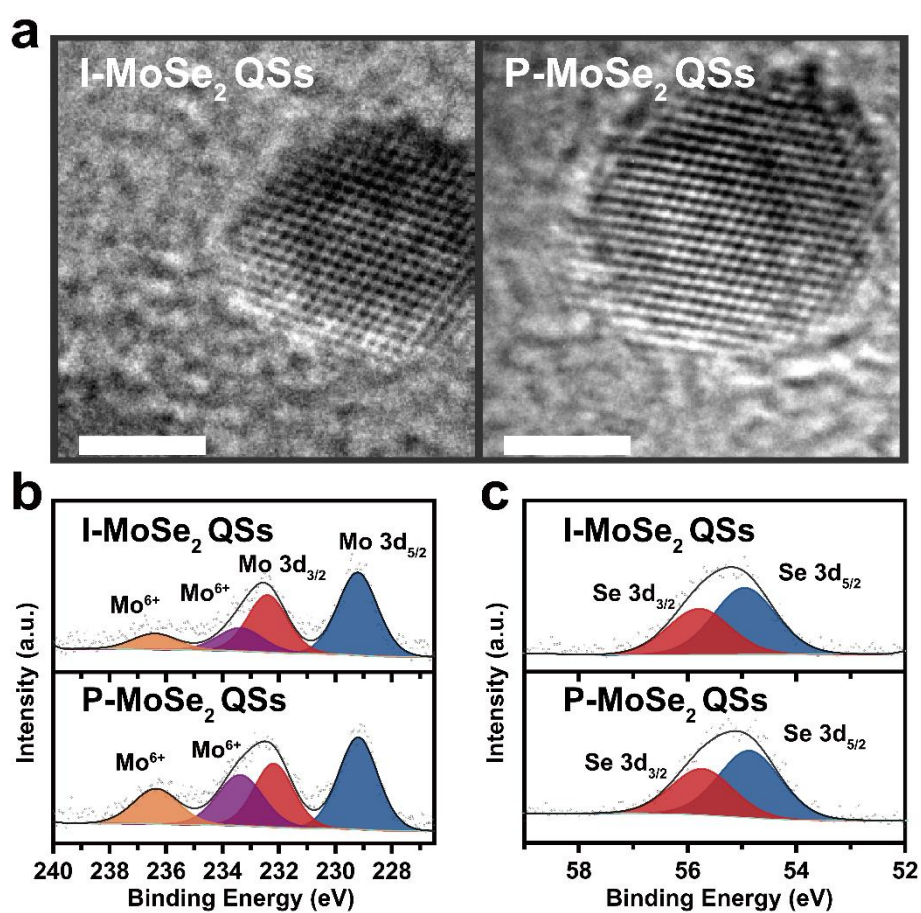


Figure S12. Structure elucidation of MoSe₂ QSs. (a) HRTEM images of MoSe₂ QSs. (b, c) XPS of MoSe₂ QSs. Scale bars in HRTEM are 2 nm.

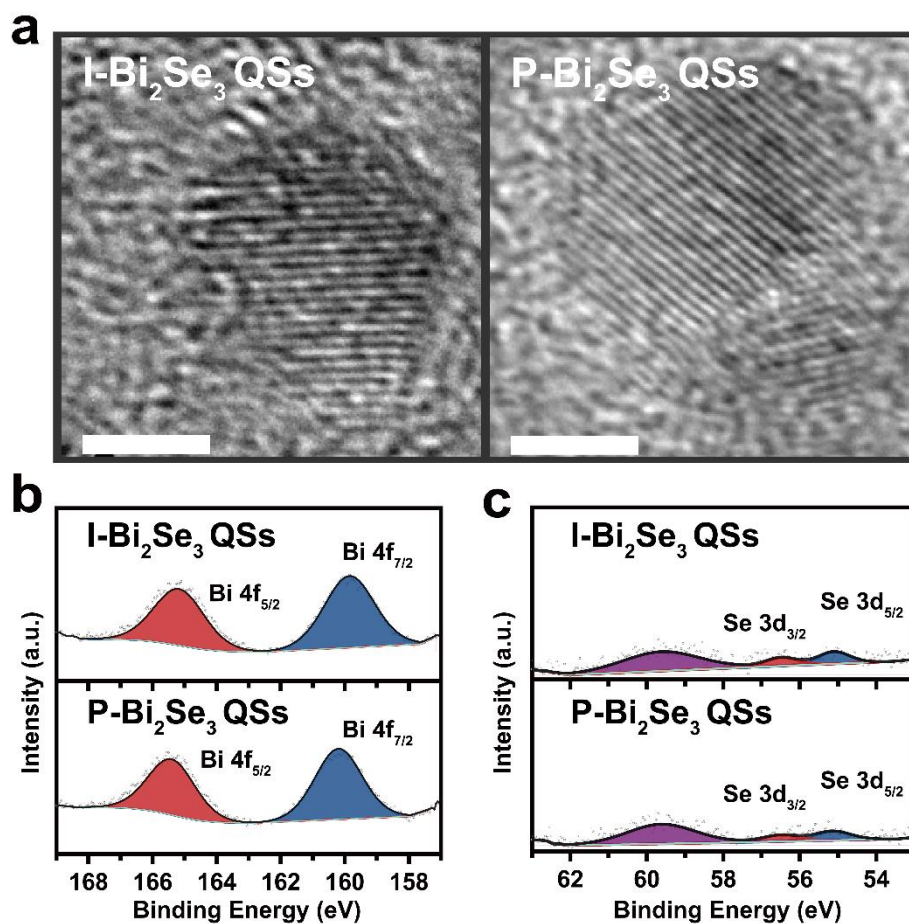


Figure S13. Structure elucidation of Bi₂Se₃ QDs. (a) HRTEM images of Bi₂Se₃ QDs. (b, c) XPS of Bi₂Se₃ QDs. Scale bars in HRTEM are 2 nm.

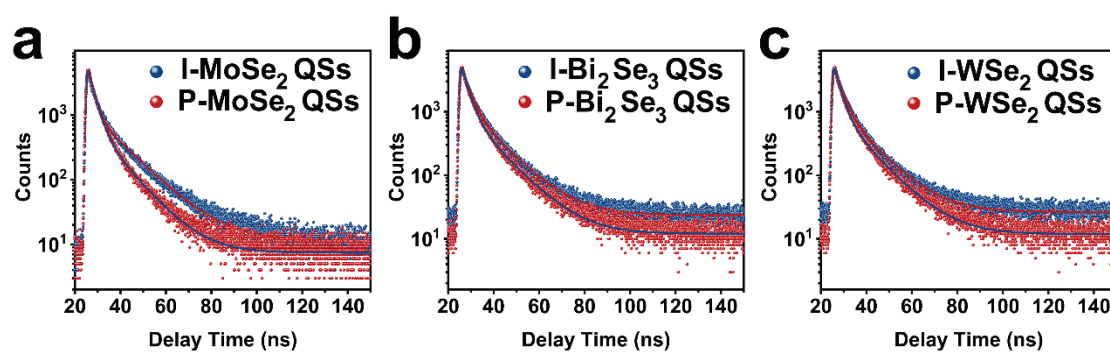


Figure S14. Lifetimes of TMD QDs. (a) MoSe₂ QDs. (b) Bi₂Se₃ QDs. (c) WSe₂ QDs.

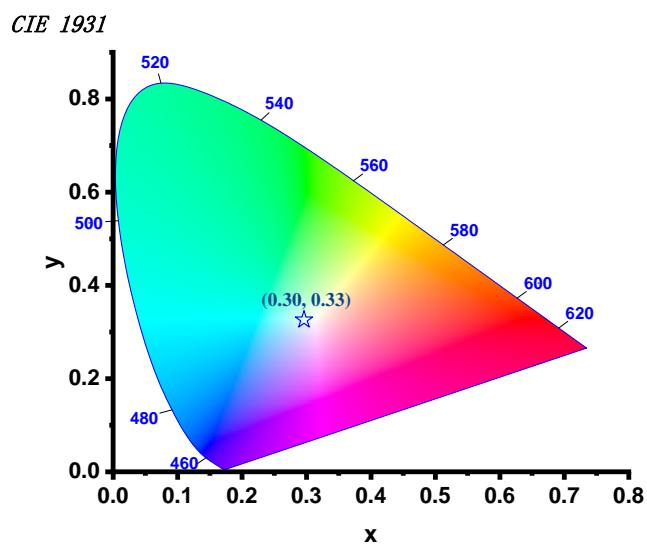


Figure S15. CIE value of P-WS₂ QSs LED.

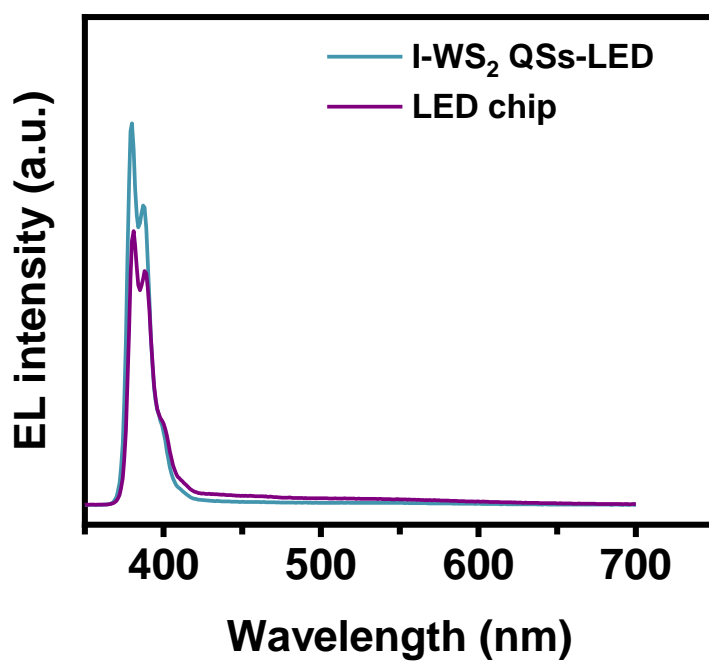


Figure S16. EL spectra of the LED chip and the I-WS₂ QSs-LED generated under a current of 10 mA.

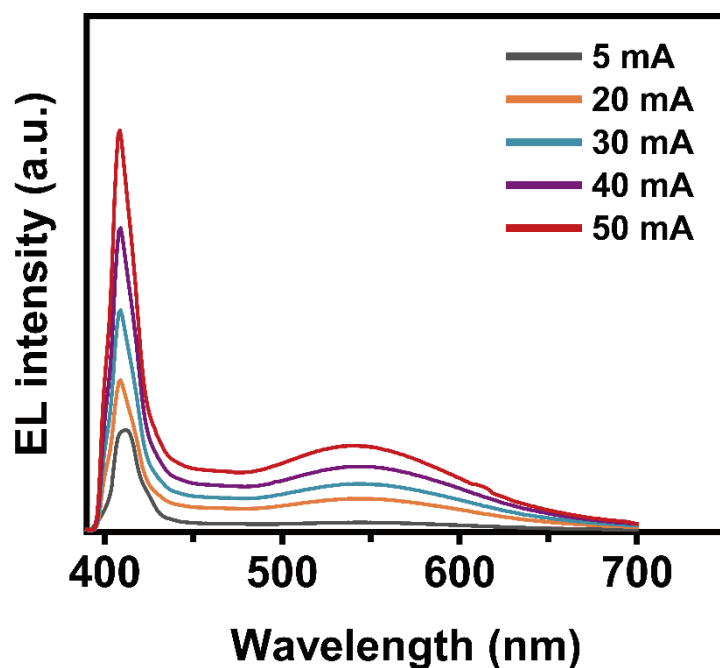


Figure S17. EL spectra of fabricated P-WS₂ QSs-LED at 5–50 mA operating currents.

Table S1. Atomic ratios obtained by partial-scan XPS spectra. X stands for W, Mo, Bi. Compared to I-QSs, the oxidation state X content of P-QSs is significantly increased. The binding energy of Bi⁴⁺ in P-Bi₂Se₃ is shifted towards higher binding energy.

X ⁶⁺ /X ⁴⁺	WS ₂	MoSe ₂	Bi ₂ Se ₃	WSe ₂
I-QSs	0	0.32	-	0
P-QSs	1.41	0.57	-	1.89

Table S2. Multiexponential fitting for time-resolved PL spectra of TMD QSs-PMMA at emission wavelength of 467 nm when excited at 370 nm.

I-QSs	WS ₂	MoSe ₂	Bi ₂ Se ₃	WSe ₂
τ_1 (ns)	2.82(46.4%)	3.42(45.1%)	3.19(46.0%)	3.12(49.7%)
τ_2 (ns)	12.80(53.6%)	12.26(54.9%)	11.63(54.0%)	11.45(50.3%)
Average (ns)	8.18	8.27	7.75	7.31

Table S3. Multiexponential fitting for time-resolved PL spectral of TMD QSs-PMMA at emission wavelength of 467 nm when excited at 370 nm. Amongst, the PL dynamics have two distinct relaxation time scales, fast and slow decays, showing the fast decay of carrier recombination in the QSs became dominant.

P-QSs	WS ₂	MoSe ₂	Bi ₂ Se ₃	WSe ₂
τ_1 (ns)	2.32(77.3%)	2.78(64.5%)	2.94(55.3%)	2.86(55.6%)
τ_2 (ns)	8.08(22.7%)	10.55(35.5%)	11.43(44.7%)	11.27(44.4%)
Average (ns)	3.63	5.54	6.74	6.59

REFERENCES

1. Xu, Y.; Chen, S.; Dou, Z.; Ma, Y.; Mi, Y.; Du, W.; Liu, Y.; Zhang, J.; Chang, J.; Liang, C.; Zhou, J.; Guo, H.; Gao, P.; Liu, X.; Che, Y.; Zhang, Y., Robust Production of 2D Quantum Sheets from Bulk Layered Materials. *Mater. Horiz.* **2019**, *6* (7), 1416-1424.